

# Resource Summary Report

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## SUSS: MicroTek MA6/BA6 Mask Aligner

RRID:SCR\_020533

Type: Tool

### Proper Citation

SUSS: MicroTek MA6/BA6 Mask Aligner (RRID:SCR\_020533)

### Resource Information

**URL:** <https://www.suss.com/brochures-datasheets/mask-aligner-ma-ba-6.pdf>

**Proper Citation:** SUSS: MicroTek MA6/BA6 Mask Aligner (RRID:SCR\_020533)

**Description:** MA/BA6 mask aligner is designed for all standard lithography applications and wafer sizes of up to 150 mm. For thick-resist MEMS applications, the MA/BA6 offers high resolution and optimum edge quality. The bottom side alignment option allows for pattern printing on both sides of the substrate. The MA/BA6 additionally provides tailored features for fragile III-V compounds, thinned or warped wafers, transparent substrates and pieces or single dies.

**Resource Type:** instrument resource

**Keywords:** SUSS Microtec, Mask Aligner, Instrument Equipment, USEDit

**Availability:** Commercially available

**Resource Name:** SUSS: MicroTek MA6/BA6 Mask Aligner

**Resource ID:** SCR\_020533

**Alternate IDs:** Model\_Number\_MA6

**Record Creation Time:** 20220129T080350+0000

**Record Last Update:** 20260725T190929+0000

### Ratings and Alerts

No rating or validation information has been found for SUSS: MicroTek MA6/BA6 Mask Aligner.

No alerts have been found for SUSS: MicroTek MA6/BA6 Mask Aligner.

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## Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.